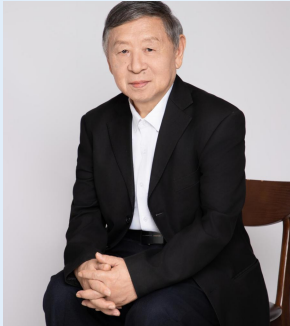


# T4. Emerging Technologies for Advanced Optical Lithography

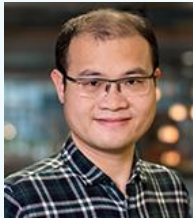
## Honorary Chair

**Dianyuan Fan**    Academician of the Chinese Academy of Engineering (CAE)



- Institute of Micro and Nano Optoelectronics, Shenzhen University, China
- International Joint Laboratory of 2D Materials for Optoelectronics Science and Technology, China
- Shanghai Institute of Optics and Fine Mechanics , CAS, China
- Defense Science and Technology Committee, CAS, China
- Commission on Defense Technology, CAS, China
- Chinese Society for Optical Engineering (CSOE), China

## Chairs & Co-Chairs



**Zizheng Cao**  
Zhejiang University, China



**Nan Lin**  
Shanghai Institute of Optics and Fine Mechanics, CAS, China



**Chenyang Ding**  
Fudan University, China



**Jing Li**  
Zhejiang University, China

## TOPICS

- Extreme Ultraviolet (EUV) Lithography
- Emerging Techniques for EUV/DUV Source
- Computational Lithography
- Metrology and Process Control
- Next-Generation Lithography Materials
- Optics for EUV/DUV Lithography

### Important Dates

Submission Deadline July 15, 2025	Notification Date August 15, 2025	Registration Deadline August 31, 2025
Camera-ready Papers Due August 31, 2025	On-site Sign in Date September 09, 2025	Main Conference Dates September 09-12, 2025

### Publication & Submission

- After a rigorous peer-review process, all accepted papers after proper registration and presentation, will be submitted for inclusion into IEEE Xplore subject to meeting IEEE Xplore's scope and quality requirements.
- Please send your manuscript to EasyChair online submission system: <https://easychair.org/conferences/?conf=ogc2025>

